

## Monolayer Graphene on 300 nm SiO<sub>2</sub>/Si

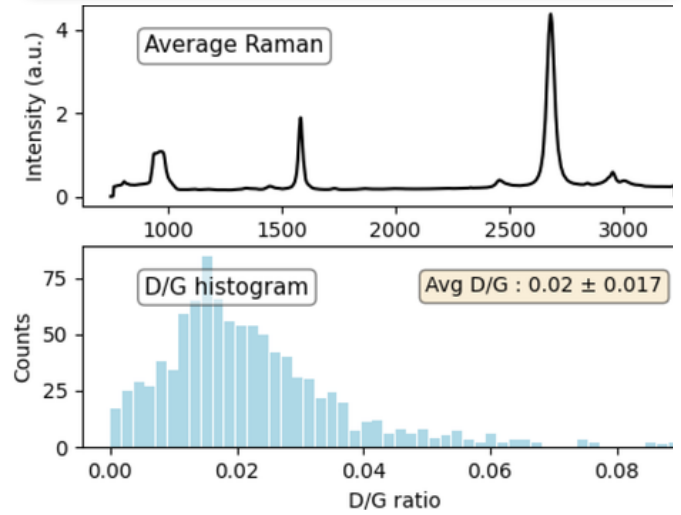
Growth Method	CVD Synthesis
Quality Control	Raman, SEM, and Optical
Transfer Method	Wet Transfer Method
Transparency	~97.7%
Graphene Thickness (Å)	3.45
Average Graphene Grain Size (µm)	~80
Multilayer Coverage (%)	< 5%
Graphene Coverage on Wafer	> 90%
I2D/IG Average - after transfer	> 1.6
ID/IG Average - after transfer	< 0.05
2D peak FWHM (cm <sup>-1</sup> ) - after transfer	~ 35
Dirac Point (mV)	220 ± 40 mV
Sheet Resistance (Ω/sq) – on SiO <sub>2</sub> /Si wafer	600 ± 50 Ω/sq
Mobility (cm <sup>2</sup> /Vs)* (dep on transfer)	2400 ± 230 cm <sup>2</sup> /Vs
Appearance	Transparent film

*[\*] Graphene on SiO<sub>2</sub>/Si wafer gated with 1X PBS solution*

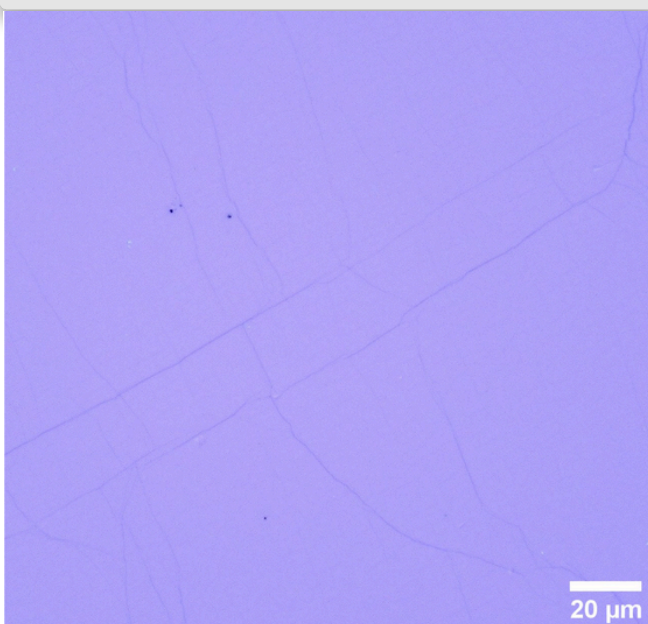
# Specifications for SiO<sub>2</sub>/Si Wafer

Diameter	100 mm
Type/Dopant	P-type (Boron)
Growth Method	CZ Prime
Orientation	<1-0-0>
Resistivity	<0.005 Ω-cm
Thickness	525 μm ± 25 μm
Film	Wet oxide on both sides, 3000 Å ± 5%
Finish	Single-side polished
Flats	2 SEMI

## Single Sample Raman Analysis



## Optical Image on Wafer



## SEM Image

